

NAME: _____

PUID: : _____

ECE 305 Exam 3: Spring 2015

March 6, 2015

Mark Lundstrom
Purdue University

This is a closed book exam. You may use a calculator and the formula sheet at the end of this exam. Following the ECE policy, the calculator **must** be a Texas Instruments TI-30X IIS scientific calculator.

There are three equally weighted questions. To receive full credit, you must **show your work** (scratch paper is attached).

The exam is designed to be taken in 50 minutes.

Be sure to fill in your name and Purdue student ID at the top of the page.

DO NOT open the exam until told to do so, and stop working immediately when time is called.

The last page is an equation sheet, which you may remove, if you want.

75 points possible, 10 per question

- 1) 25 points (5 point per part)
- 2) 25 points (5 points per part)
- 3) 25 points (5 points per part)

----- Course policy -----

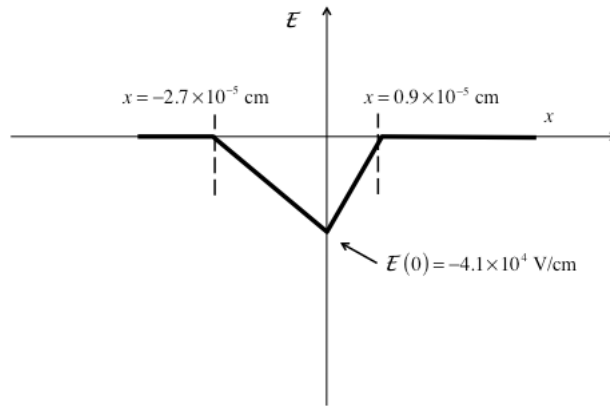
I understand that if I am caught cheating in this course, I will earn an F for the course and be reported to the Dean of Students.

Read and understood: _____
signature

Answer the **five multiple choice questions** below by **drawing a circle** around the **one, best answer**.

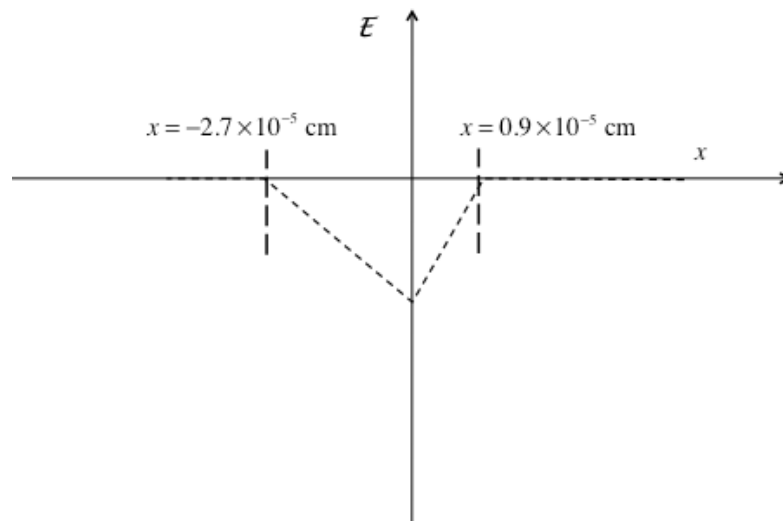
- 1a) What is $\Delta n = \left(n_i^2 / N_A \right) \left(e^{qV_A / k_B T} - 1 \right)$ called?
- The Einstein relation .
 - The Caughey-Thomas relation.
 - The second law of thermodynamics.
 - Moore's Law
 - The Law of the Junction.
- 1b) What is the primary reason for the strong temperature dependence of the diode saturation current, I_0 , in an NP junction with $N_D \gg N_A$?
- The D_n term in I_0 .
 - The L_n term in I_0 .
 - The N_A term in I_0 .
 - The n_i^2 term in I_0 .
 - None of the above.
- 1c) What is the physical meaning of the area under $\mathcal{E}(x)$ vs. x in equilibrium?
- It is the total doping density in the transition region.
 - It is equal to the bandgap of the semiconductor.
 - It is the net space-charge density in the transition region.
 - It is the net dipole moment of the junction.
 - It is the built-in potential of the junction.
- 1d) Ion implantation is a technique to do what?
- Dope a semiconductor.
 - Deposit an insulating layer on a semiconductor.
 - Deposit a metallic layer on a semiconductor.
 - Deposit an insulating layer on an insulator.
 - Deposit a metallic layer on an insulator.
- 1e) What is "lithography" used for in semiconductor manufacturing?
- To dope semiconductors.
 - To deposit amorphous films on semiconductors.
 - To deposit polycrystalline films on semiconductors.
 - To grow crystalline films on semiconductors.
 - To produce patterns in the films deposited on semiconductors.

- 2) The electric field vs. position for a Si junction in equilibrium is sketched below. (The depletion approximation is assumed). Given the information provided, answer the following questions.



- 2a) What is the built-in voltage for this junction?

- 2b) Assume that a reverse bias of magnitude $V_R = 3V_{bi}$ is applied to this junction. Sketch the electric field versus position being careful to indicate the values on the vertical and horizontal axes. (The dotted line is the equilibrium electric field.) Briefly explain your answer.

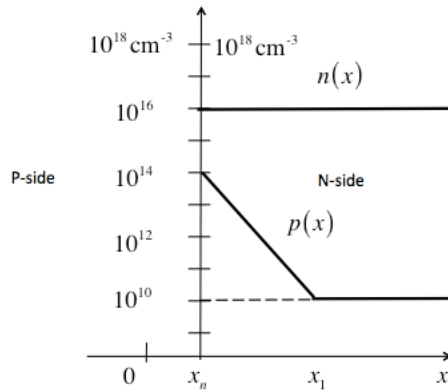


2c) What is the doping density on the N-side? (Hint: You will first need to determine which is the N-side.)

2d) What is the doping density on the P-side?

2e) If the voltage in equilibrium is zero at $x = 0.9 \times 10^{-5}$ cm, then what is the voltage at $x = 0$?

- 3) The sketch below shows the carrier concentrations in a PN junction at room temperature. Only the quasi-neutral N-side of the junction is shown. Answer the following questions.



- 3a) Is the junction forward or reverse biased? Explain your answer.
- 3b) Is the N-side of this PN junction "long" or "short". Explain your answer.
- 3c) What is the intrinsic carrier concentration?

3d) What voltage is applied to this diode?

3e) At what location, x , where $x \geq x_n$, is the splitting of the quasi-Fermi levels the biggest? Explain your answer.